



## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

# Amos a 9/15/01 V.Varnall

In re Application of: Liu, et al.

Art Unit: 2825

Serial No.: 09/575,055

Examiner: Chuong A. Luu

Filed: May 19, 2000

For: "Method for Selective Fabrication of High Capacitance Density Areas in a Low Dielectric Constant

Material and Related Structure"

## **AMENDMENT AND RESPONSE**

Honorable Commissioner of Patents and Trademarks Washington, D.C. 20231

Dear Sir/Madam:

This is in response to the Office Action dated August 28, 2001 in the above-referenced patent application. Please enter and consider the following amendments and remarks.

## In the Claims:

Please cancel claims 24-27.